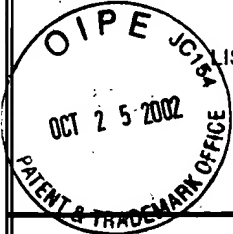
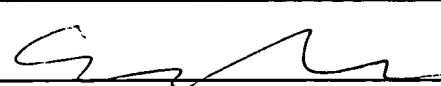

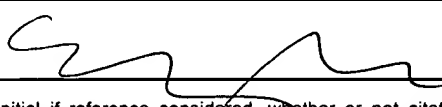


Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2042		SERIAL NO. 09/579,402		
 LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Kei-Yu Ko				
				FILING DATE May 25, 2000		GROUP 2815		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
EL	AA	5,269,879	12/14/93	Rhoades et al.	156	643		
EL	AB	5,298,465	03/29/94	Levy	437	225		
EL	AC	5,658,425	08/19/97	Halman et al.	438	620		
EL	AD	5,685,914	11/11/97	Hills et al.	118	723		
EL	AE	5,780,338	07/14/98	Jeng et al.	438	253		
EL	AF	5,783,496	07/21/98	Flanner et al.	438	743		
EL	AG	5,817,579	10/06/98	Ko et al.	438	740		
EL	AH	5,830,807	11/03/98	Matsunaga et al.	438	714		
EL	AI	5,871,659	02/16/99	Sakano et al.	216	79		
EL	AJ	5,908,320	06/01/99	Chu et al.	437	743		
EL	AK	5,946,568	08/31/99	Hsiao et al.	438	253		
EL	AL	6,074,488	06/13/00	Roderick et al.	118	728		
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
EL	AM	0 680 084 A1	28.04.95	EPO (Texas Instruments Inc.)				
EL	AN	WO 98/49719	05.11.98	WIPO (Micron Technology, Inc.)				
	AO							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
EL	AP		Abatchev et al., <i>Study of the Boron-Phosphorous Doped and Undoped Silicate Glass Etching in</i>					
			CHF3/Ar Plasma, 96 ELECTROCHEM. SOC. PROCEEDINGS, No. 12, pp. 522-530 (1996).					
	AQ							
EXAMINER				DATE CONSIDERED				
				3/10/03				
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

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<div style="display: flex; align-items: center;"> <div style="border: 2px solid black; border-radius: 50%; padding: 10px; text-align: center; margin-right: 10px;"> OIP E OCT 25 2002 PATENT & TRADEMARK OFFICE </div> <div> <p>LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p> </div> </div>				APPLICANT: Kei-Yu Ko			
				FILING DATE May 25, 2000	GROUP 2815		
U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
EL	AA	6,074,958	06/13/00	Tokunaga et al.	438	724	RECEIVED OCT 29 2002 TC 2800 MAIL ROOM
EL	AB	6,117,788	09/12/00	Ko	438	706	
EL	AC	6,117,791	09/12/00	Ko et al.	438	723	
EL	AD	6,121,671	09/19/00	Ko et al.	257	644	
EL	AE	6,153,490	11/28/00	Xing et al.	438	396	
EL	AF	6,159,862	12/12/00	Yamada et al.	438	712	
EL	AG	6,165,880	12/26/00	Yaung et al.	438	592	
EL	AH	6,171,970 B1	01/09/01	Xing et al.	438	706	
EL	AI	6,174,451 B1	01/16/01	Hung et al.	216	67	
EL	AJ	6,183,655 B1	02/06/01	Wang et al.	438	723	
EL	AK	6,254,966 B1	07/03/01	Kondo	428	156	
EL	AL	6,337,285 B1	01/08/02	Ko	438	714	
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
AM							
AN							
AO							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AP						
	AQ						
EXAMINER				DATE CONSIDERED 3/16/03			
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<div style="text-align: center;">  </div> <p style="text-align: center;">LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p>				APPLICANT: Kei-Yu Ko				
				FILING DATE May 25, 2000		GROUP 2815		
U.S. PATENT DOCUMENTS								
*Examiner Initial	AA	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
AL	AA	6,432,833 B1	08/13/02	Ko	438	714		
EL	AB	6,458,685 B1	10/01/02	Ko et al.	438	621		
EL	AC	09/532,088		Ko			03/21/2000	
EL	AD	09/945,508		Ko			08/30/2001	
	AE							
	AF							
	AG							
	AH							
	AI							
	AJ							
	AK							
	AL							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM							
	AN							
	AO							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AP							
	AQ							
EXAMINER 				DATE CONSIDERED 3/10/03				
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<div style="position: relative; height: 100px;"> <div style="position: absolute; top: 0; left: 0; width: 100%; height: 100%; border: 1px solid black; border-radius: 50%; text-align: center; line-height: 100px; font-size: 24px; font-weight: bold;"> DIPE DEC 04 2002 PATENT & TRADEMARK OFFICE </div> </div>				LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)			
				APPLICANT: Kei-Yu Ko			
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U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
EL	AA	5,883,436	03/16/99	Sadjadi et al.	257	760	
EL	AB	6,277,758 B1	08/21/01	Ko	438	706	
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
EL	AK	61-133555	12.03.84	Japan (NEC, Ltd.)			X	
EL	AL	0 465 044 A2	19.06.91	EPO (AT&T)				
EL	AM	0 496 614 A1	23.01.92	EPO (NEC Corp.)				
EL	AN	0 763 850 A1	30.08.96	EPO (Applied Materials)				
	AO							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
EL	AP		W.G.M. van den Hoek et al., <i>Isotropic plasma etching of doped and undoped silicon dioxide for contact holes and vias</i> , 7 J. VAC. SCI. TECHNOL. A., No. 3, pp. 670-675 (May/June 1989).
	AQ		
	AR		

EXAMINER	DATE CONSIDERED 3/10/03
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